

WWW. IGANPOWER.COM 230 -3410 LOUGHEED HWY VANCOUVER, BC, V5M 2A4 CANADA

GPI65007DF

N-channel 650V 7A GaN Power HEMT in DFN 5X6 Package

Datasheet version 2.5 Preliminary

Features

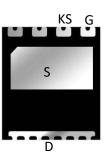
BV _{dss}	R _{dson}	l _{ds}	$Q_{\rm g}$
650 V	170 mΩ	7 A	2.1 nC

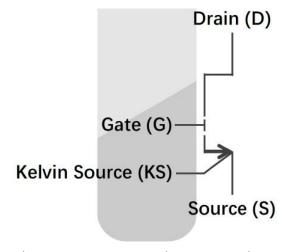
- Ultra-low RDS(on)
- · High dv/dt capability
- Extremely low input capacitance
- · Zero Qrr
- · Outstanding switching performance
- · Low Profile

Applications

- · Switching Power Applications
- · Adapters, Quick Chargers







Description

These devices are N-channel 650 V Power GaN HEMTs based on proprietary E-mode GaN on silicon technology. The resulting product has extremely low on state resistance, very low input capacitance and zero reverse recovery charge making it especially suitable for applications which require superior power density, ultra-high switching frequency and outstanding efficiency.



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Device Characteristics

Sta	Static Parameters			Test data			
	Parameters		Conditions	Min	Typical	Max	Unit
1	V	Cata threshold voltage	V _{ds} =V _{gs} , I _d =3.5 mA (T _J =25 °C)	1.0	1.2	1.5	V
	V _{gs(TH)} Gate threshold voltage	Gate threshold voltage	V _{ds} =V _{gs} , I _d =3.5mA (T _J =150 °C)		1.15		V
2	BV_dss	Drain-Source breakdown voltage	$V_{gs} = 0V, I_{d} < 20 \mu A$ $(T_{J} = 25 °C)$		650		V
3	l _{dss}	Zero gate voltage drain leakage current	$V_{gs} = 0V, V_{ds} = 650V$ $T_{J} = 25 ^{\circ}C$	0.05	0.06	0.08	μД
4	I _{gss}	Gate-Source Leakage	$V_{gs} = 6V, V_{ds} = 0V$		6	80	μд
_	D		$V_{gs} = 6V, I_{d} = 2.5A$ $T_{J} = 25 ^{\circ}C$		170	190	mΩ
5	R _{dson}	drain-source on resistance	V_{gs} =6V, I_{d} =2.5A T_{J} = 150 °C		360		mΩ
6	V_{sd}	Reverse conduction voltage	I _{sd} =1A, V _{gs} =0V	1.7	1.9	2.3	V
7	R _g	Gate resistance	f=25Mhz Open drain		1.5		Ω
Dyr	Dynamic Parameters			Test data			
	Parameters		Conditions	Min	Typical	Max	Unit
1	C _{ISS}	Input capacitance	V _{gs} = 0V		76.1		pf
2	C _{OSS}	Output capacitance	V _{ds} = 400V		20.9		pf
3	C _{RSS}	Reverse transfer capacitance	F = 1MHz		0.42		pf
4	CO(er)	Effective output capacitance, energy related	Vds = 0 - 400V		35		pf
5	Qg	Gate charge	Vds = 400V		2.1		nC
6	Q_{gs}	Gate to source charge	Id = 1.75A		0.4		nC
7	Q_{gd}	Gate to drain charge	Vgs = 6V		0.52		nC
8	QOSS	Output Charge	Vds = 0 - 400V		22		nC
9	Q _{rr}	Reverse recovery charge			0		nC



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Switching Performance		Test data					
	Parameters		Conditions	Min Typical Max Unit		Unit	
1	t _{d(on)}	Turn-on delay time	V _{ds} = 400V		4		ns
2	t _r	Rise time	I _d = 1.75A		8		ns
3	t _{d(off)}	Turn-off delay time	$R_g = 10\Omega$		14		ns
4	t _f	Fall time	V _{gs} = 6V		8		ns

Absolute Max. Ratings

	Symbols	Parameters	Value	Unit
1	$V_{\text{DS-max}}$	Breakdown voltage transient @ T _{case} =25°C	800	V
2	V_{DS-max}	Breakdown voltage transient @ T _{case} =125°C	650	V
3	V_{GS-max}	Gate to source max. voltage @ T _{case} =25°C	-12 to +7.5	V
4	I _{ds-max}	Drain to source pulse current @ T_{case} =25°C, pulse width 10 μ s, V_{GS} = 6 V	16	А
5	I _{ds-max}	Drain to source pulse current @ T _{case} =150°C	7	Α
6	dv/dt _{-max}	Drain to source voltage slew rate	200	V/ns
7	T_{J-max}	Max junction temperature	150	°C
8	$T_{S-storage}$	Storage temperature	-55 to 150	°C

Thermal and Soldering Characteristics (Typical)

	Symbols	Parameters	Value	Unit
1	R_{thJC}	Thermal resistance (junction to case)	2.2	°C /W
2	R_{thJA}	Thermal resistance (junction to ambient)	62	°C /W
3	T _{solder}	Reflow soldering temperature	250	°C

Ordering

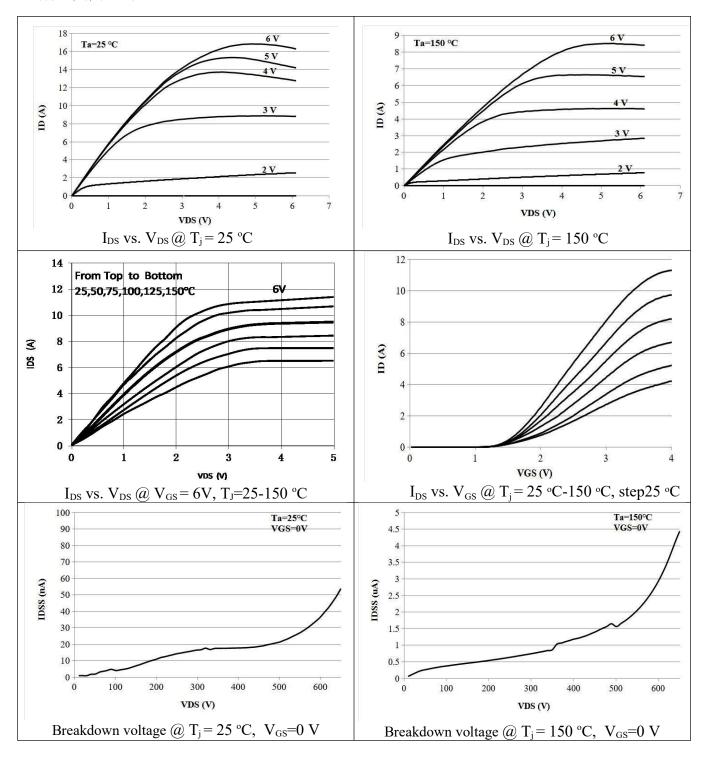
Order Code	Package Type	Packaging Method	Qty
GPI65007DF	DFN surface mount, bottom cooled, 5X6 mm		

Electrical Performance



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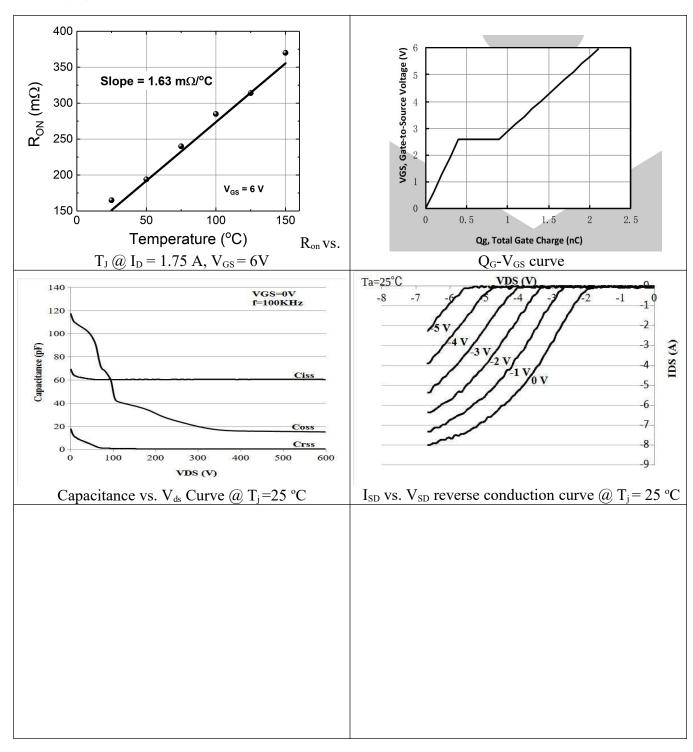
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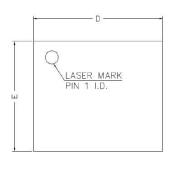


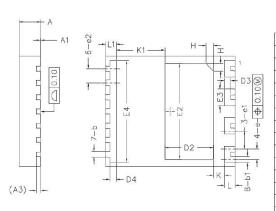


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Package Information





COMMON DIMENSIONS (UNITS OF MEASURE=MILLIMETER)

SYMBOL	MIN	NOM	MAX
А	0.90	1.00	1.10
A1	0.00	0.02	0.05
A3	0.203REF		
b	0.20	0.25	0.30
b1	0.225	0.275	0.325
D	5.90	6.00	6.10
D E	4.90	5.00	5.10
D2	2.15	2.25	2.35
E2	4.27	4.37	4.47
D3	0.20	0.30	0.40
E3	0.65	0.75	0.85
D4	0.20	0.30	0.40
E4	4.525	4.625	4.725
е	0.375	0.475	0.575
e1	0.725	0.825	0.925
e2	0.55	0.65	0.75
Н	0.35REF		
K	0.35	0.50	0.65
K1	2.10	2.25	2.40
<u>P.</u>	0.40	0.50	0.60
L1	0.40	0.50	0.60

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GaN HEMT Frequently Asked Questions

1	Q: Can we do pin to pin switch for silicon MOSFET or IGBT? A: The short answer is no. GaN HEMT power devices are far superior than the best silicon devices such as super junction MOSFETs. However, due to different requirements of gate driving voltage and extremely high dv/dt slew rate, special drivers and optimized PCB layouts are recommended to minimize the impact from circuit parasitics.
2	Q: How do GaN power devices compare with SiC? A: Currently GaN power HEMT devices are most suitable for low to medium voltage (≤1200V) and power (<20KW) applications. GaN is the ideal choice for high frequency applications. SiC devices are better choice for high voltage and high-power applications (>20KW).
3	Q: Do we need to parallel an FRD for applications such as inverters? A: GaN devices are different from silicon MOSFET or IGBT in that they have no inherent PN junction diodes that cause reverse recovery issue. User do not need to parallel an FRD for the purpose of suppressing the body diode reverse recovery effect, since GaN HEMT can operate in both first and third quadrants. However, care should be taken for the dead time power loss since the Vsd voltage of GaN HEMT is usually close to 2V. This is especially true when a negative gate voltage is applied.
4	Q: Can we parallel GaN HEMT devices? A: Yes, GaN HEMT is ideal for paralleling, due to the positive temperature coefficient of R _{ds,on} . Hence, paralleling GaN HEMT devices are encouraged.